

Supporting Information (SI) for:

**Facile *In-Situ* Synthesis of Crystalline VOOH-Coated VS<sub>2</sub> Microflowers with Superior Sodium Storage Performance**

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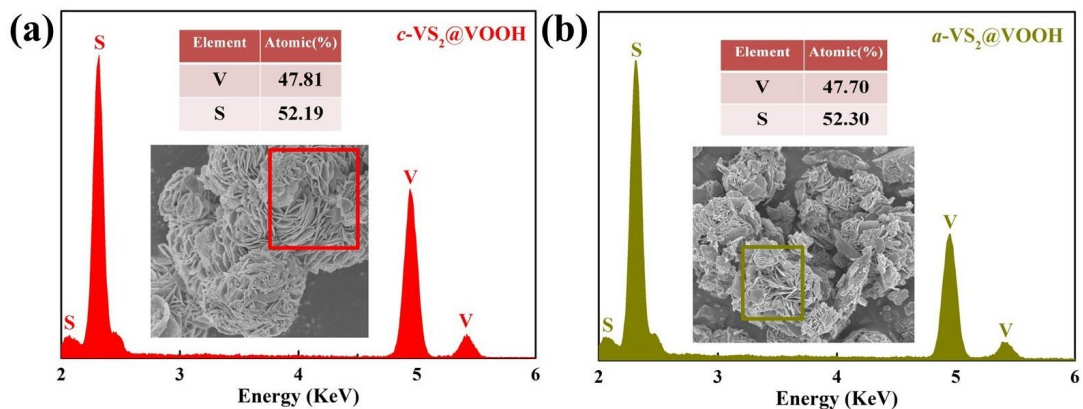


Fig. S1 EDS spectra of (a) *c*-VS<sub>2</sub>@VOOH microflowers and (b) *a*-VS<sub>2</sub>@VOOH microflowers obtained by SEM-EDS.

The weight percent of VOOH in VS<sub>2</sub>@VOOH is calculated by the following equation:

$$W_{\text{VOOH}} = \frac{(A_{\text{V}} - A_{\text{S}}/2) \times M_{\text{VOOH}}}{(A_{\text{V}} - A_{\text{S}}/2) \times M_{\text{VOOH}} + A_{\text{S}}/2 \times M_{\text{VS}_2}} \times 100\%$$

where  $W_{\text{VOOH}}$  is the weight percent of VOOH in VS<sub>2</sub>@VOOH.  $A_{\text{V}}$  and  $A_{\text{S}}$  are the atomic percent of V and S, respectively.  $M_{\text{VOOH}}$  and  $M_{\text{VS}_2}$  are the molar mass of VOOH and VS<sub>2</sub>, respectively.

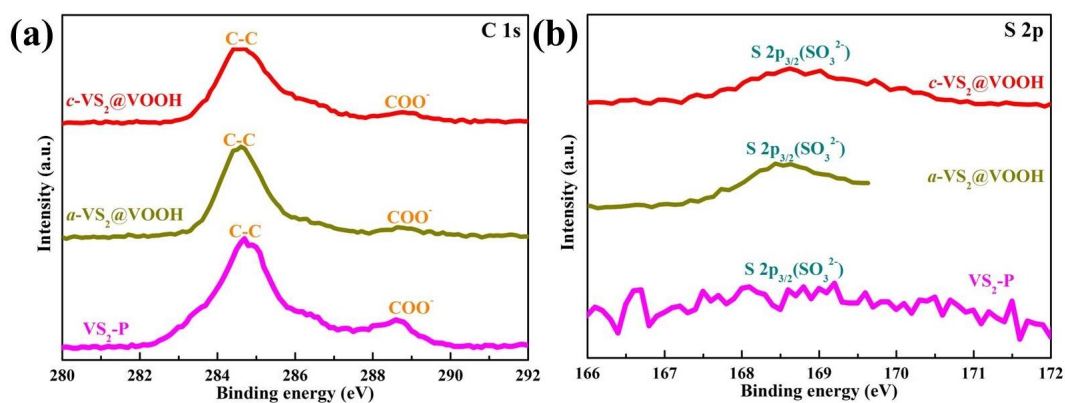


Fig. S2 High resolution (a) C 1s and (b) S 2p XPS spectra for *c*-VS<sub>2</sub>@VOOH, *a*-VS<sub>2</sub>@VOOH and VS<sub>2</sub>-P.

The binding energy at  $\sim 288.9$  eV in Fig. S2(a) further shows the existence of COO<sup>-</sup>,<sup>2</sup> and the value of  $\sim 168.8$  eV in Fig. S2(b) is consistent with the reported value for S<sup>4+</sup> in S 2p spectral region<sup>3,4</sup>, further declaring the existence of SO<sub>3</sub><sup>2-</sup> groups.

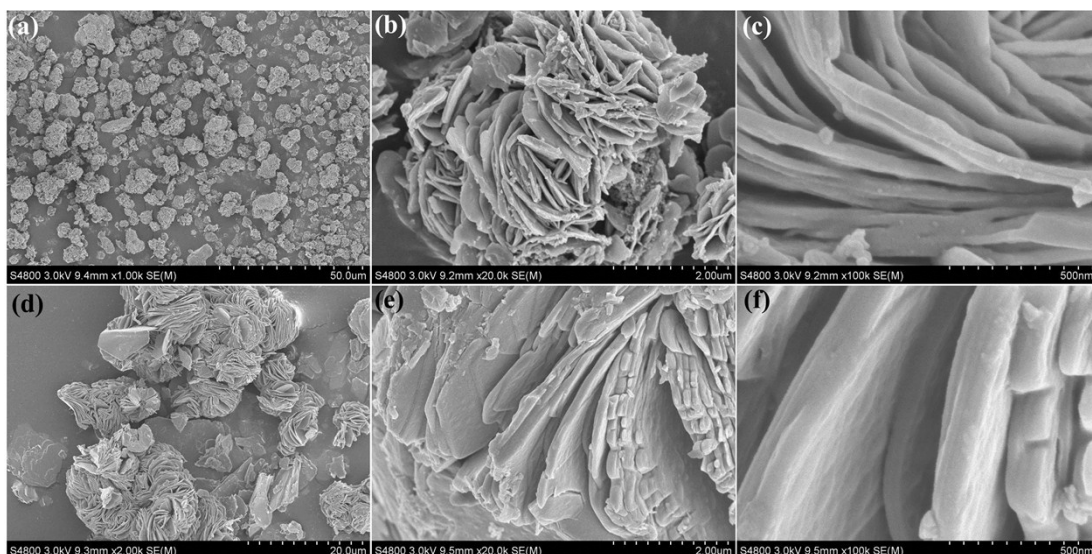


Fig. S3 SEM images of (a ~ c)  $a\text{-VS}_2\text{@VOOH}$  and (d ~ f)  $\text{VS}_2\text{-P}$ .

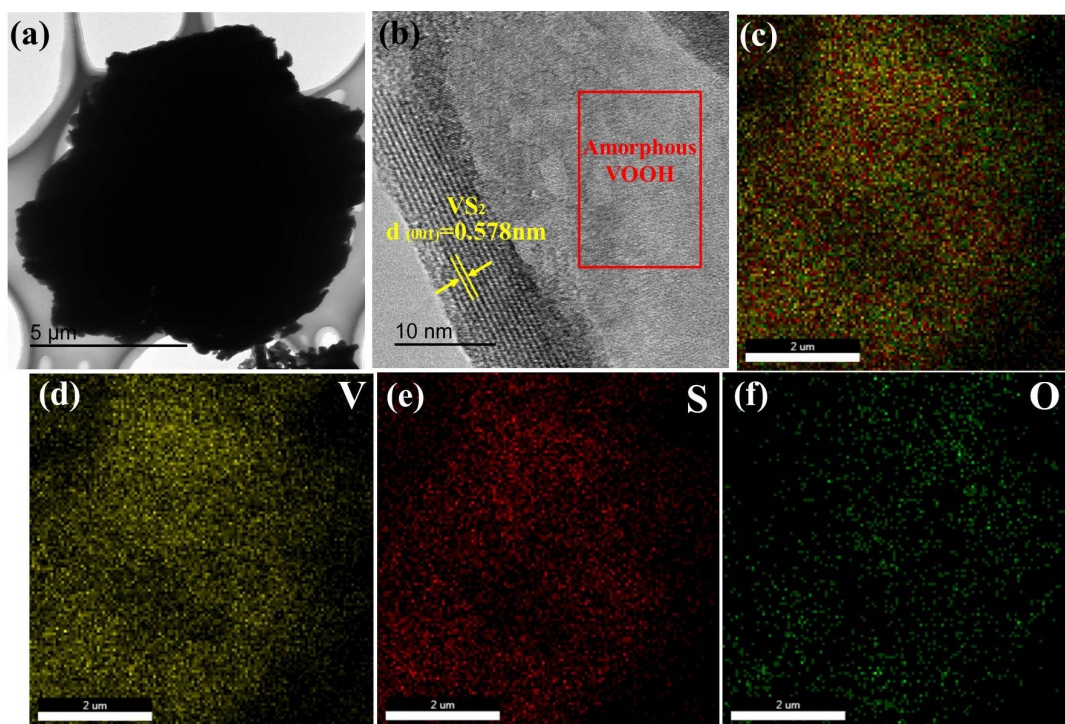


Fig. S4 (a) Low-magnification TEM image, (b) HRTEM image and (c ~ f) elemental mapping images of  $a\text{-VS}_2\text{@VOOH}$  microflower.

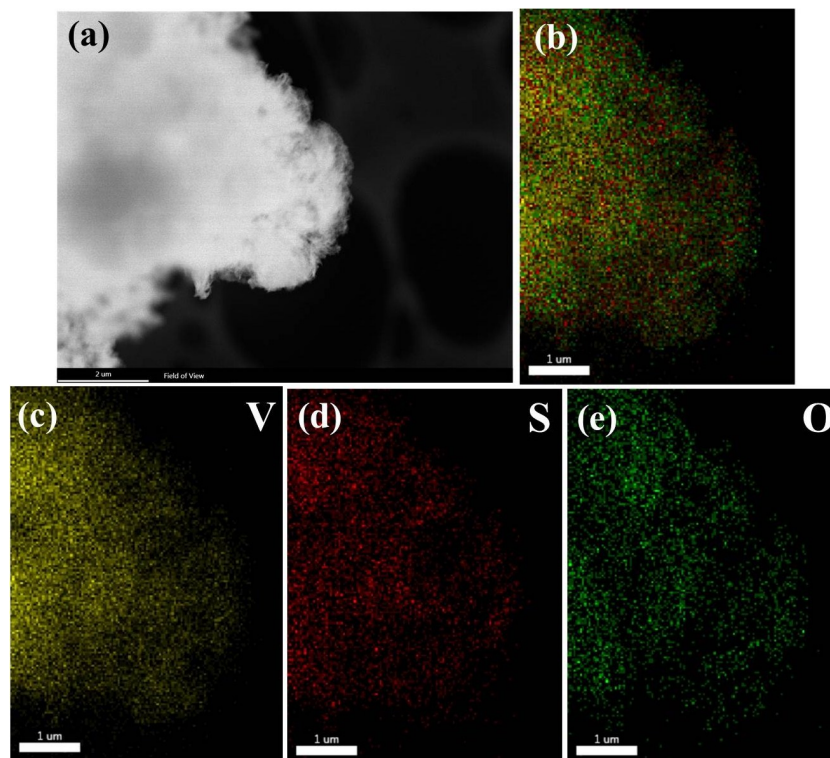


Fig. S5 (a) STEM image and (b ~ e) the corresponding elemental mapping images of  $c\text{-VS}_2\text{@VOOH}$  microflower.

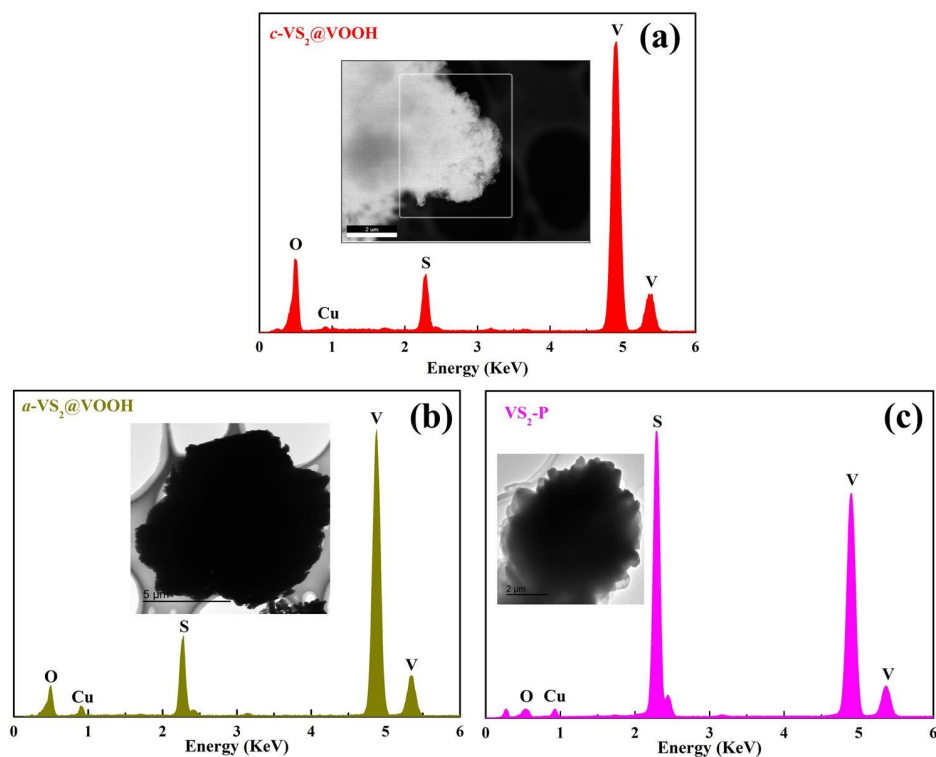


Fig. S6 EDS spectra of the map scanning corresponding to the low-magnification TEM images of (a)  $c\text{-VS}_2\text{@VOOH}$ , (b)  $a\text{-VS}_2\text{@VOOH}$  and (c)  $\text{VS}_2\text{-P}$ , which were obtained by STEM-EDS with the detection depth of  $\sim 10$  nm.

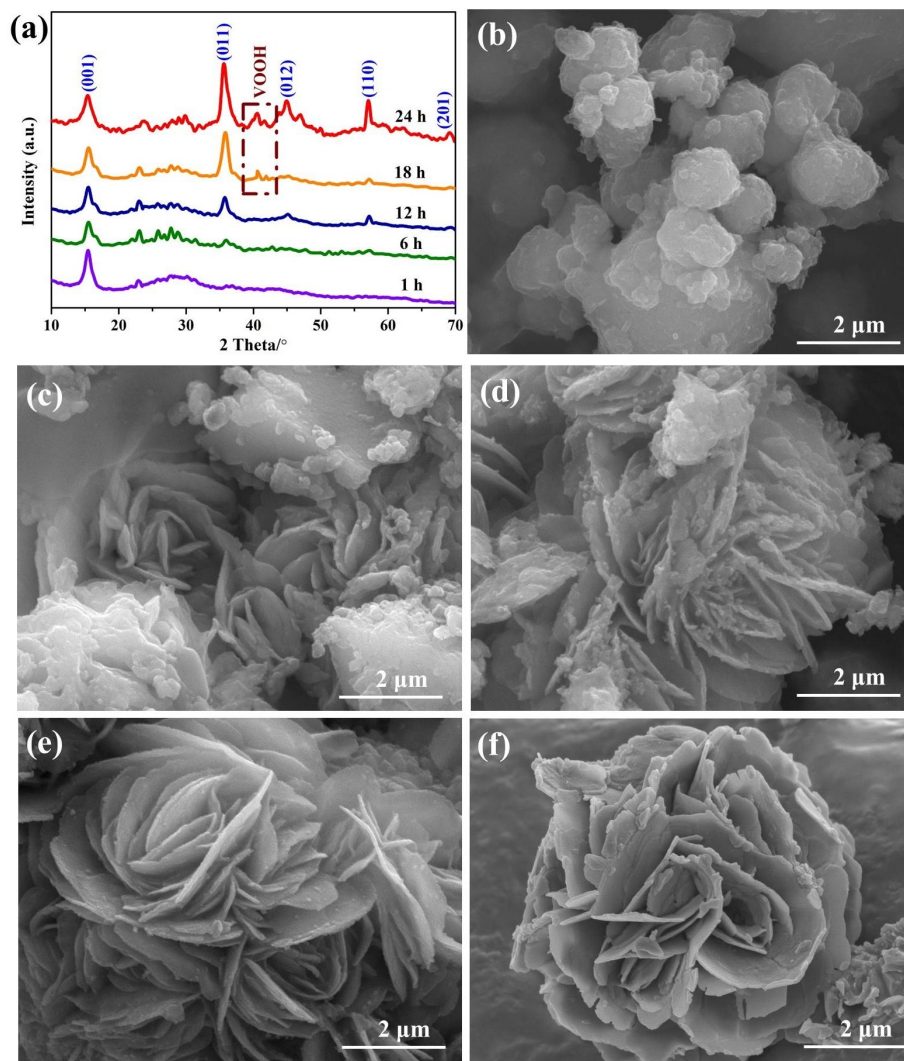


Fig. S7 (a) XRD patterns, and (b ~ f) SEM images of the products prepared at 1, 6, 12, 18 and 24 h, respectively.

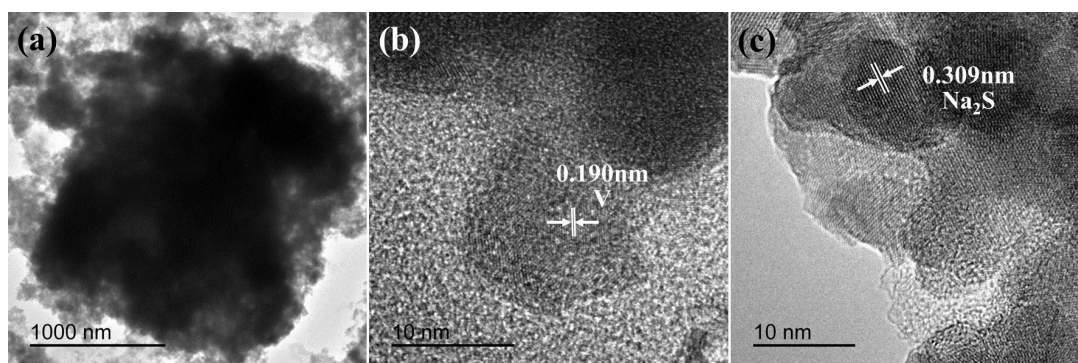


Fig. S8 TEM and HRTEM images of  $c\text{-VS}_2\text{@VOOH}$  electrode materials after discharging to 0.05 V at  $0.05 \text{ Ag}^{-1}$ .

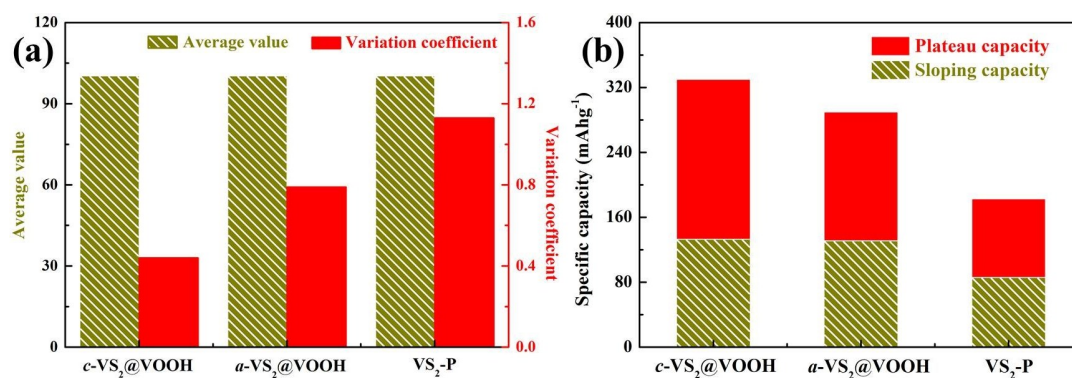


Fig. S9 (a) Average values and variation coefficients of the CEs derived from Fig. 8(b) and (b) plateau capacities and sloping capacities of the charge profiles in Fig. 8(c).

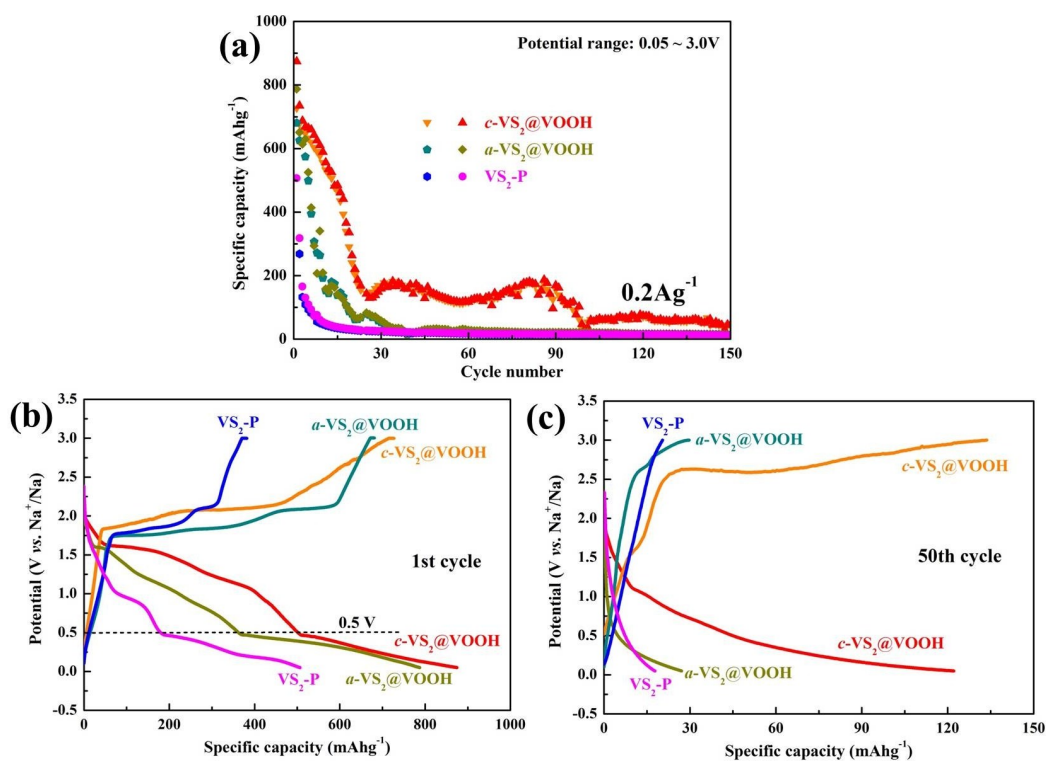


Fig. S10 (a) Cycling performances at the potential range of 0.05 ~ 3.00 V and corresponding to charge/discharge profiles after (b) 1 cycle and (c) 50 cycles for  $c\text{-VS}_2\text{@VOOH}$ ,  $a\text{-VS}_2\text{@VOOH}$  and  $\text{VS}_2\text{-P}$ .

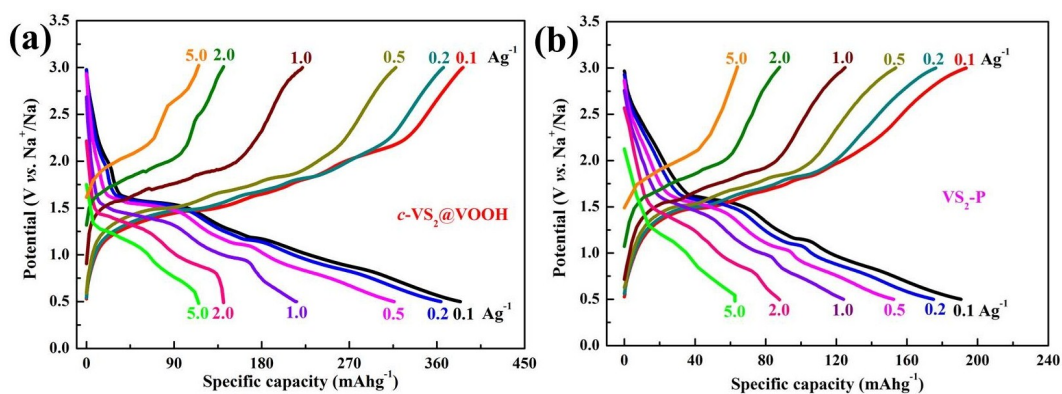


Fig. S11 Charge/discharge profiles of (a)  $c\text{-VS}_2\text{@VOOH}$  and (b)  $\text{VS}_2\text{-P}$  at various current densities from 0.1 to 5.0  $\text{Ag}^{-1}$ .



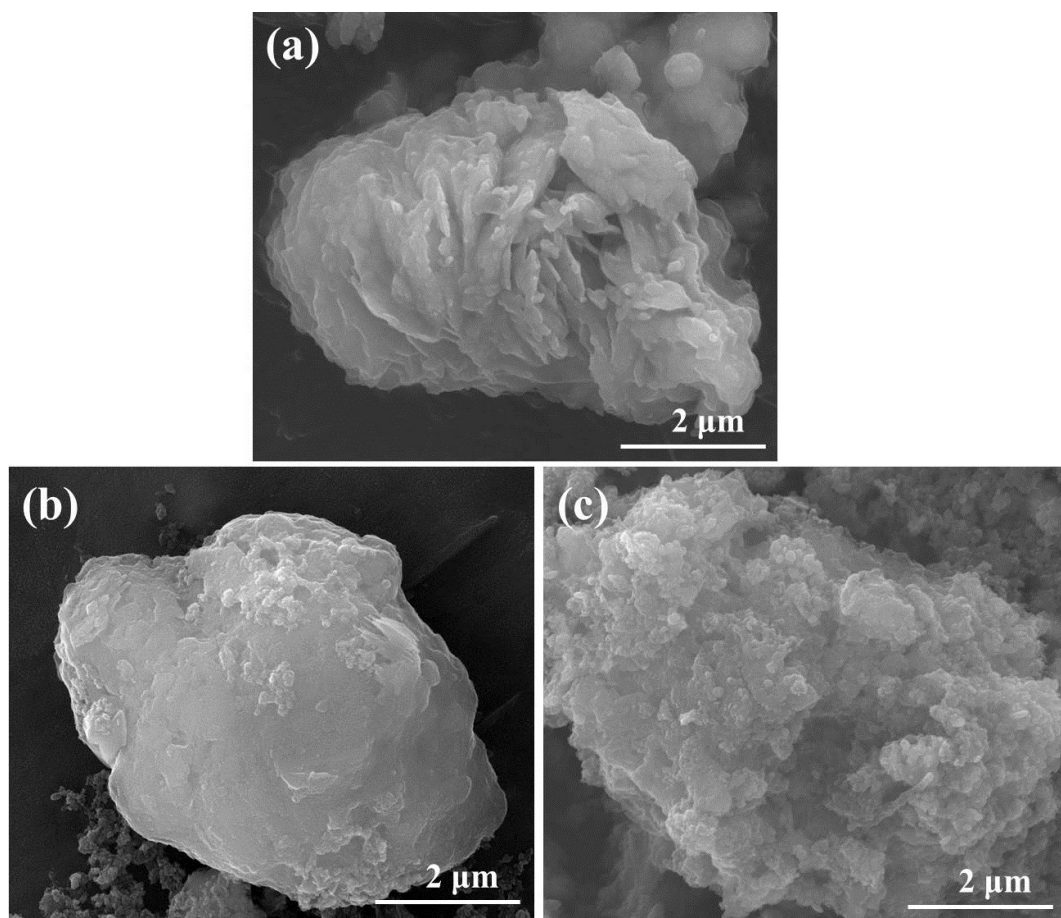


Fig. S12 SEM images of (a)  $c\text{-VS}_2\text{@VOOH}$ , (b)  $a\text{-VS}_2\text{@VOOH}$  and (c)  $\text{VS}_2\text{-P}$  electrode materials at  $0.2 \text{ Ag}^{-1}$  after 150 cycles.

Table S1 Electrochemical performance comparison of the as-prepared *c*-VS<sub>2</sub>@VOOH-based with other V-based and TMDs-based anode materials of SIBs.

Materials	Current density, Ag <sup>-1</sup>	Cycling capacity, mAhg <sup>-1</sup> , (cycle number, n)	Rate capacity, mAhg <sup>-1</sup> , (Current density, Ag <sup>-1</sup> )	Cut-off voltage (V)	Active material loading, mg·cm <sup>2</sup>	Electrode composition	Ref
<b><i>c</i>-VS<sub>2</sub>@VOOH</b>	<b>0.2</b>	<b>330(150)</b>	<b>424(0.1), 404(0.2), 356(0.5), 224(1.0), 140(2.0), 113(5.0)</b>	<b>0.5~3.0</b>	<b>0.6~1.0</b>	<b>8:1:1</b>	<b>This work</b>
VS <sub>2</sub>	0.2	245(100)	252(0.1), 211(0.5), 201(1.0), 196(2.0), 203(5.0)	0.4~2.2	0.84~1.05	7:2:1	5
ce-VS <sub>2</sub>	1.0	109(100)	----	0.01~3.0	~1.0	7:2:1	2
VS <sub>2</sub> @Na <sub>2</sub> Ti <sub>2</sub> O <sub>5</sub>	0.2	203(50)	233(0.1), 210(0.4), 161(1.0), 124(2.0), 75(4.0)	0.01~3.0	1.0~1.5	----	6
VS <sub>4</sub> /rGO	0.5	149(100)	341(0.1), 267(0.3), 220(0.5), 192(0.8)	0.01~2.2	0.84~1.05	7:2:1	7
ce-V <sub>5</sub> S <sub>8</sub> -C	1.0	496(500)	682(0.1), 643(0.2), 616(0.5), 584(1.0), 485(2.0), 389(5.0), 437(0.05), 375(0.1),	0.01~3.0	~1.0	7:2:1	2
VSe <sub>2</sub> /C	0.1	467(50)	326(0.2), 309(0.5), 263(1.0), 132(2.0)	0~3.0	----	8:1:1	8
V <sub>2</sub> O <sub>5</sub>	0.04	177(100)	200(0.04), 185(0.08), 157(0.16), 130(0.32), 122(0.64)	1.0~4.0	~0.88mg	8:1:1	9

VO <sub>2</sub> /rGO	0.4	123(200)	196(0.04), 178(0.08), 160(0.16), 134(0.4), 108(0.8)	0.25~3.0	----	8:1:1	10
FeV <sub>2</sub> S <sub>4</sub>	0.075	529(10)	548(0.075), 480(0.15), 372(0.375)	0~3.0	~3.0	8:1:1	11
MoS <sub>2</sub>	0.32	234 (100)	498(0.04), 441(0.08), 409(0.16), 305(0.32)	0.01~3.0	~0.84	7:2:1	12
FeS <sub>2</sub>	0.2	256(60)	202(1.0)	0.8~3.0	----	8:1:0.4:0.6	13
WS <sub>2</sub> NWs	0.5	362(500)	415(0.2), 370(0.5), 330(1.0)	0.5~3.0	----	7.5:1.5:1	14
ce-NbS <sub>2</sub>	0.5	157(100)	205(0.1), 185(0.2), 170(0.5), 137(1.0), 106(2.0), 93(5.0)	0.01~3.0	~0.7	7:2:1	15
NiS <sub>2</sub> - GNs	0.1	313(200)	375(0.08), 325(0.16), 278(0.4), 221(0.8), 168 (1.6)	0.01~3.0	----	7:2:1	16
TiS <sub>2</sub>	0.48	141(300)	189(0.048), 180(0.12), 148(0.48), 123(1.2), 100(2.4)	1.0~3.0	----	8:1:1	17
CoS <sub>2</sub> - MWCNT	0.1	568(100)	727(0.1), 687(0.2), 621(0.4), 550(0.8)	1.0~2.9	----	8:1:1	18

The list of electrode composition ratio contains the active material, the conductive material and the binder.

----: The relevant data is not mentioned in the article.

Table S2 Resistance values simulated from modeling the experimental impedance (Fig. 10) using the equivalent circuit shown in the inset in the bottom right of Fig. 10(a).

Sample	$R_s$ ( $\Omega$ )	$R_f+R_{ct}$ ( $\Omega$ )	$Z_w$ ( $\Omega \cdot S^{1/2}$ )
<i>c</i> -VS <sub>2</sub> @VOOH	11.7	7.9	42
<i>a</i> -VS <sub>2</sub> @VOOH	22.4	22.0	87
VS <sub>2</sub> -P	54.0	86.7	123

$R_s$  is the electrolyte resistance.  $R_f$  is the SEI film resistance.  $R_{ct}$  is the charge-transfer resistance from electrolyte to active materials.  $Z_w$  is the Warburg resistance.

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